

Confirmation No.: 1603 Martin, et al.

Group Art Unit: 1763 Serial No.: 09/855,972

Examiner: Hassanzadeh, Parvis Filed: May 15, 2001

Docket No. 062002-1751

Method and Apparatus for Low Energy Electron Enhanced Etching of For:

Substrates in an AC or DC Plasma Environment

AMENDMENT AFTER ALLOWANCE

Mail Stop Issue Fee P.O. Box 1450 Commissioner for Patents Alexandria, Virginia 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.312, please enter the following amendments. Applicants respectfully submit that the amendments herein merely embody the correction of formal matters and do not alter the scope or substance of the application.

It is not believed that extensions of time or fees for net addition of claims are required, beyond those, which may otherwise be provided for in documents accompanying this paper. However, in the event that additional extensions of time are necessary to allow consideration of this paper, such extensions are hereby petitioned under 37 C.F.R. § 1.136(a), and any fees required therefor (including fees for net addition of claims) are hereby authorized to be charged to deposit account no. 20-0778.